PTO/SB/08b (02-09)

Approved for use through 03/12009. OMB 0851-0031

U.S. Patent and Trademank Office, U.S. DEPARTMENT OF COMMERCE

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

Subst	Substitute for form 1449/PTO			Complete if Known		
0000	and to form 14401 10			Application Number	10/534,200-Conf. #5266	
IN	FORMATIO	N DI	SCLOSURE	Filing Date	November 7, 2002	
ST	TATEMENT	BY A	APPLICANT	First Named Inventor	Palaniappan Meiyappan	
-				Art Unit	2617	
	(Use as many sheets as necessary)			Examiner Name	S. T. Zewari	
Sheet	1	of	2	Attorney Docket Number	68144/P020US.B/10505125	

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No.1	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear

FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No.1	Foreign Patent Document Country Code ³ -Number ⁴ -Kind Code ⁶ (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages Or Relevant Figures Appear	
/S.Z./	ВА	JP-08-256,103 (English Abstract)	Oct. 01, 1996	Hitachi Denshi Ltd.		

NON PATENT LITERATURE DOCUMENTS				
Examiner Initials	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T²	
1971	CA	Japanese Office Action Issued for JP2004-551367, dated January 6, 2009, 3 pages.		

Examiner	(Court Zourri)	Date	10/11/0000
Signature	/Saved Zewari/	Considered	10/14/2009

**EXAMINES* Initial if reference considering, whether or not claiston is in conformance with MEPE 600. Draw here through claimful in information and consideration in the conformation and consideration in the composition of the conformation and consideration in the conformation and conformation